

10/088306
JC10 Rec'd PCT/PTO 18 MAR 2002

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Hiromoto OHNO, et al.

Appln. No.: National Stage of PCT/JP01/06164

Confirmation No.: NOT YET ASSIGNED

Group Art Unit: NOT YET ASSIGNED

Filed: March 18, 2002

Examiner: NOT YET ASSIGNED

For: CLEANING GAS FOR SEMICONDUCTOR PRODUCTION EQUIPMENT

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Page 1, under "CROSS-REFERENCE TO RELATED APPLICATIONS" delete
the first full paragraph and insert the following:

This application is based on the provisions of 35 U.S.C. Article 111(a) with claiming the
benefit of filing dates of U.S. provisional application Serial No. 60/230,811 filed on September
7, 2000 and U.S. provisional application Serial No. 60/261,265 filed on January 16, 2001 under
the provisions of 35 U.S.C. 111(b), pursuant to 35 U.S.C. Article 119(e)(1).

IN THE CLAIMS:

Please enter the following amended claims:

2. (Amended) The cleaning gas for semiconductor production equipment as

claimed in claim 1, comprising SF₆, F₂, and an inert gas.